A Composite TE-TFE-FE Model for Schottky Barrier Reverse Current over the Entire Electric-Field Range

Wenshen Li¹, Debdeep Jena^{1,2,3}, and Huili Grace Xing^{1,2,3}

¹School of Electrical and Computer Engineering, ²Department of Materials Science and Engineering ³Kavli Institute at Cornell for Nanoscale Science, Cornell University, Ithaca, NY 14853, USA;

Email: <u>wl552@cornell.edu</u> / Phone: (412)500-1493

Introduction:

Schottky barriers in wide bandgap (WBG) semiconductors can sustain very large electric fields under reverse bias due to the access of very large barrier heights (>1 eV) and the very high intrinsic breakdown field (>3 MV/cm) of WBG semiconductors [1]. Under high surface electric-fields (*E*), the ideal reverse-bias leakage current (J_R) is dominated by barrier tunneling rather than thermionic emission (TE), thus thermionic-field-emission (TFE) or field-emission (FE) becomes the dominant mechanism [1][2]. Therefore, to accurately describe the reverse current over the entire surface electric-field range, TFE and FE models are required in addition to the TE model.

We have recently developed a unified TE-TFE model that covers the entire TE and TFE regimes [3], however, the model is not applicable in the FE regime, the same goes for all other stand-alone TFE models. On the other hand, the well-known Murphy-Good FE model works well in the FE regime [2], but it is not applicable in the TFE regime. As a result, a gap exists in the TFE-to-FE transition region, as illustrated in **Fig. 1**, where no good analytical model exists. There has been an attempt to derive a unified TFE and FE model, however, the model is based on highly simplified emission integral with questionable accuracy, and image-force lowering is ignored [4]. In this context, we present a simple composite analytical model that covers the entire *E*-field range with excellent accuracy, with the use of an empirically-derived extrapolation function in the TFE-to-FE transition region.

Methods:

The integral for the barrier tunneling current under reverse bias is analytical intractable in the TFE-to-FE transition region [2]. To overcome this difficulty and knowing that the TE/TFE region and the FE region are well-described by the unified TE-TFE model [1] and Murphy-Good FE model [2][5], respectively (see **Fig. 1**), we seek to find an appropriate extrapolation function for the TFE-to-FE transition region. Based on the dominant exponential dependence of the TFE and FE models, it can be shown that leading term of $d(\sqrt{E} \ln J_R)/dE$ undergoes a transition from $E^{3/2}$ to $E^{-3/2}$ in the TFE-to-FE transition region, which means that $d(\sqrt{E} \ln J_R)/dE \sim E^0$ in the transition region. This has been confirmed empirically by numerical calculations, as shown in **Fig. 2a**. Thus, it is appropriate to adopt a linear relationship between $\sqrt{E} \ln J_R$ and E in the transition region, where the current is defined as J_{trans} (**Fig. 3**). The linear coefficients therein are determined by two J_R values, J_1 and J_2 , calculated at the upper *E*-limit of the unified TE-TFE model ($E_{\text{ulim,TFE}}$) and at the lower *E*-limit of the Murphy-Good FE model ($E_{\text{llim,FE}}$), respectively (see **Fig. 1b**). To ensure good accuracy of the extrapolation function for J_{trans} , the conditions for $E_{\text{ulim,TFE}}$ and $E_{\text{llim,FE}}$ have been modified with more strict requirements, as shown in **Fig. 4**. These modified conditions yield improved accuracy for J_1 and J_2 , which in turn, enables a more accurate extrapolation function in the transition region.

Results and Discussion:

Comparisons between the composite TE-TFE-FE model relative to the reference numerical model [1] is shown in **Fig. 5**. The log error across the entire *E*-field range is within 2 dB (equivalent to a factor of 1.25) (**Fig. 2c**). The first derivative also shows very good agreement with the numerical model (**Fig. 2b**), indicating the extrapolation function for J_{trans} allows for a smooth transition between TFE and FE. We have used the composite model to analyze the reverse leakage characteristics in near-ideal 4H-SiC SBDs [6] and Ga₂O₃ SBDs [1]. Very good agreement between experimental data and the composite model is observed across both the TE/TFE and the FE regimes, with the barrier height as the only fitting parameter (**Fig. 6**). Such an accurate analysis over the entire temperature and surface electric-field range is only possible with numerical calculations previously, as illustrated in **Table I**.

Conclusion: The composite TE-TFE-FE model successfully bridges the gap between the unified TE-TFE model and the Murphy-Good FE model with a simple empirical extrapolation function, allowing for accurate modeling of the Schottky barrier reverse current across the entire electric-field range. The closed-form and local nature of the composite model allows for easy implementation in TCAD tools for device design and analysis.

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Fig. 1. (a) Illustration of the TE/TFE regime and the FE regime. Unified TE-TFE [3] and Murphy-Good FE [2] models both have limited applicable range. (b) Definition of J_1 , J_2 , E_1 and E_2 in the new composite model.



Fig. 2. First derivative of (a) $\sqrt{E} \ln J_{\rm R}$ and (b) $J_{\rm R}$. The former shows $d(\sqrt{E} \ln J_{\rm R})/dE \sim E^0$ in the TFE-to-FE transition region, justifying the empirical form of $J_{\rm trans}$. (c) Log error $|20\log_{10}(J_{\rm R}/J_{\rm R,ref})|$ relative to the numerical model $(J_{\rm R,ref})$. $(\phi_{\rm B}=1.3 \text{ V}, m^*=0.3 m_0, \varepsilon_{\rm s}=10 \varepsilon_0)$.

Main equations



Fig. 3. Main equations for the composite TE-TFE-FE model.



Fig. 4. Modified conditions for $E_{\text{ulim},\text{TFE}}$ and $E_{\text{llim},\text{FE}}$ in the composite model with improved accuracy.

Fig. 5. The composite model exhibits excellent agreement against the reference numerical model [1].

TABLE I. Comparison of different models applicable at the FE regime

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	F-N tunneling	Murphy- Good FE [2]	Unified TFE-FE [4]	Numerical model [1]	This work
Temperature dependence	No	Yes	Yes	Yes	Yes
Image-force lowering	Yes	Yes	No	Yes	Yes
Entire <i>E</i> -field range	Yes	No	Yes	Yes	Yes
Closed-form expression	Yes	Yes	Yes	No	Yes
Doping effect*	No	No	No	Yes	No

*Insignificant below ~1×1018 cm-3



Fig. 6. Analysis of near-ideal reverse leakage characteristics in (a) 4H-SiC SBDs [6] and (b) β -Ga₂O₃ SBDs [1] using the composite model, with the barrier height as the only fitting parameter.

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